



Atty. Dkt. No.	M#	Client Ref.
	273243	PC0033A 2

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: JOHNSON et al.	
Appln. No.: 10/076,099	
Filing Date: February 15, 2002	
Examiner: Not Assigned	Group Art Unit: 1762

Date: July 19, 2002 Page 1 of 4

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
<i>fm</i>	AR	5,688,357	11/1997	HANAWA	156	345.29	
	BR	4,993,358	02/1991	MAHAWILI	118	715	
	CR	4,935,661	06/1990	HEINECKE et al.	313	23.31	
	DR	4,891,118	01/1990	OOIWA et al.	204	296.34	
	ER	4,824,690	04/1989	HEINECKE et al.	427	577	
	FR	4,500,563	02/1985	ELLENBERGER et al.	427	710	
	GR	4,413,022	11/1983	SUNTOLA et al.	117	95	
	HR	4,401,507	08/1983	ENGLE	438	2000	
	IR	4,263,088	04/1981	GORIN	117	95	
	JR	4,058,430	11/1977	SUNTOLA et al.	117	95	
	KR	3,979,235	09/1976	BOUCHER	427	569	
	LR	3,721,583	12/1970	BLAKESLEE	117	95	
	MR	3,677,799	11/1970	HOU	427	569	
<i>fm</i>	NR	5,164,040	11/1992	ERES et al.	427	608	

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28
10/31/05

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract	Translation Readily Available
						Enclosed	No
	OR						
	PR						
	QR						

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

<i>fm</i>	RR	Bird, Molecular Gas Dynamics and the Direct Simulation of Gas Flows, Claredon Press, 1994, pp. 2-3.			
	SR	Gentry et al., "Ten-microsecond pulsed molecular beam source and a fast ionization detector," Rev. Sci. Instru, 49(5), May 1978, pp. 595-600.			
	TR	Samukawa et al., "Pulse-time modulated electron cyclotron resonance plasma etching for highly selective, highly anisotropic, and less-charging polycrystalline silicon patterning," J. Vac. Sci. Technol. B 12(6), Nov/Dec 1994, pp. 3300-3305.			
	UR	Sugai et al., "Diagnostics and control of high-density etching plasmas," Mat. Res. Soc. Symp., Proc. Vol 406, 1996, pp. 15-25.			
	VR	Yeon et al., "Study of particulate formation and its control by a radio frequency power modulation in the reactive ion process of SiO2 with CF4/H2 Plasma" J. Vac. Sci. Technol. A 15(1), Jan/Feb 1997, pp. 66-71.			
<i>fm</i>	WR	Bates, et al., "Fast gas injection system for plasma physics experiments," Rev. Sci. Instrum. 55(6) June 1984, pp. 934-939.			

Examiner: <i>Forney</i>	Date Considered: <i>9/9/03</i>
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*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.